

ABSTRACT OF THE DISCLOSURE

In order to enable perpendicular processing of a slice in all directions about a lens optical axis, a focused charged particle beam of the present invention is provided with a tilt mechanism capable of tilting in two axial directions below a three dimensional X, Y, Z drive mechanism, as sample stage drive means. In this way, when carrying out correction processing of a clear defect of a penetrating structure in an electron beam exposure mask, it is possible to accurately carry out perpendicular processing of pattern surfaces in all directions.